

## Refine Search

### Search Results -

Terms	Documents
L4 and (glass near5 transition)	22

Database:

US Pre-Grant Publication Full-Text Database  
 US Patents Full-Text Database  
 US OCR Full-Text Database  
 EPO Abstracts Database  
 JPO Abstracts Database  
 Derwent World Patents Index  
 IBM Technical Disclosure Bulletins

Search:

L5



Refine Search

Recall Text



Clear

Interrupt

### Search History

DATE: Monday, September 19, 2005   [Printable Copy](#)   [Create Case](#)

#### Set Name Query

side by side

#### Hit Count Set Name

result set

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

<u>L5</u>	L4 and (glass near5 transition)	22	<u>L5</u>
<u>L4</u>	L3 and ((second or first) near5 (resist or photoresist))	196	<u>L4</u>
<u>L3</u>	L2 and ((pattern\$ or develop) same (resist or photoresist))	339	<u>L3</u>
<u>L2</u>	L1 and (anti reflect\$ or antireflect\$ or ARC)	921	<u>L2</u>
<u>L1</u>	((resist or photoresist) near3 flow\$) or RFP	11387	<u>L1</u>

END OF SEARCH HISTORY